

(19) World Intellectual Property
Organization
International Bureau



(43) International Publication Date
2 June 2005 (02.06.2005)

PCT

(10) International Publication Number
WO 2005/050317 A3

(51) International Patent Classification⁷: **G03F 1/14**, 7/20

(21) International Application Number:
PCT/US2004/038899

(22) International Filing Date:
18 November 2004 (18.11.2004)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
10/715,955 18 November 2003 (18.11.2003) US

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(81) Designated States (unless otherwise indicated, for every
kind of national protection available): AE, AG, AL, AM,
AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN,

CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI,
GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE,
KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD,
MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG,
PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM,
TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM,
ZW.

(84) Designated States (unless otherwise indicated, for every
kind of regional protection available): ARIPO (BW, GH,
GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM,
ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM),
European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI,
FR, GB, GR, HU, IE, IS, IT, LU, MC, NL, PL, PT, RO, SE,
SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ,
GW, ML, MR, NE, SN, TD, TG).

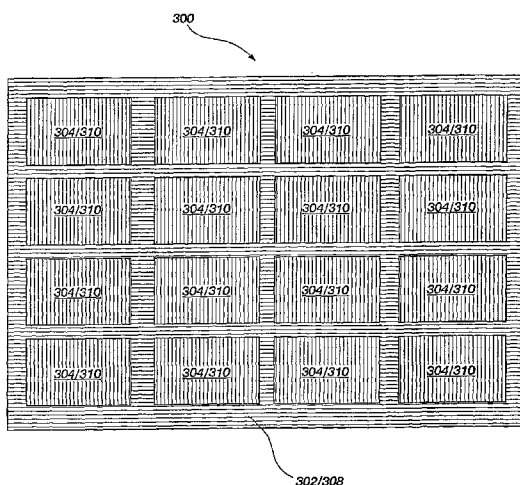
Published:

- with international search report
- before the expiration of the time limit for amending the
claims and to be republished in the event of receipt of
amendments

(88) Date of publication of the international search report:
22 September 2005

For two-letter codes and other abbreviations, refer to the "Guid-
ance Notes on Codes and Abbreviations" appearing at the begin-
ning of each regular issue of the PCT Gazette.

(54) Title: POLARIZED RETICLE, PHOTOLITHOGRAPHY SYSTEM, AND METHOD OF FORMING A PATTERN USING
A POLARIZED RETICLE IN CONJUNCTION WITH POLARIZED LIGHT



(57) Abstract: Polarized reticles, photolithography systems utilizing a polarized reticle, and methods of using such a system are disclosed. A polarized reticle is formed having a reticle containing at least one first patterned region at least partially surrounded by at least one second patterned region. The first patterned region of the polarized reticle includes a polarized material and the second patterned region of the polarized reticle also includes a polarized material. Polarization directions of the polarized materials of the two regions are generally orthogonal to each other. When the polarized reticle is irradiated using linear polarized light having a selected polarization direction, the polarized materials on the two regions of the polarized reticle may be selectively used as a filter to enable exposing the different regions of the polarized reticle separately under optimal illumination conditions.

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